


FIG. 1a

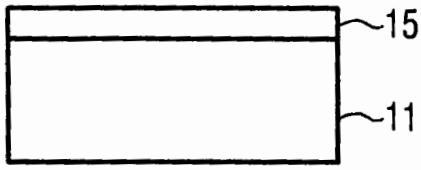



FIG. 1b

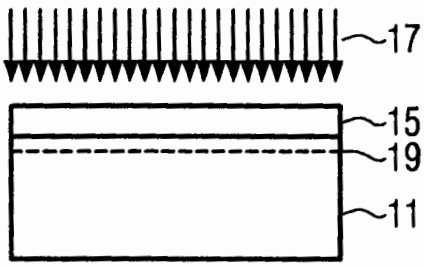



FIG. 1c

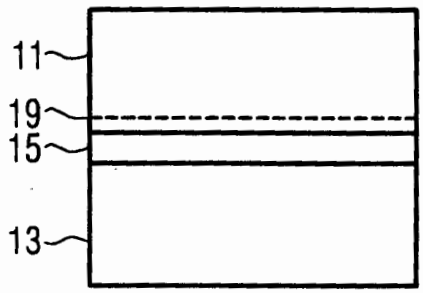



FIG. 1d

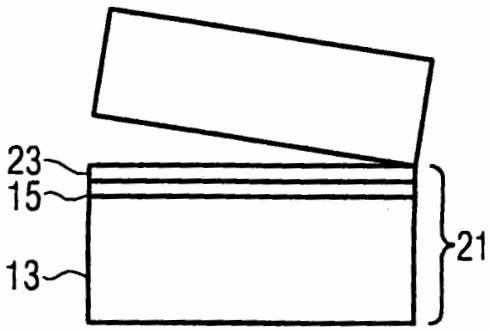



FIG. 1e

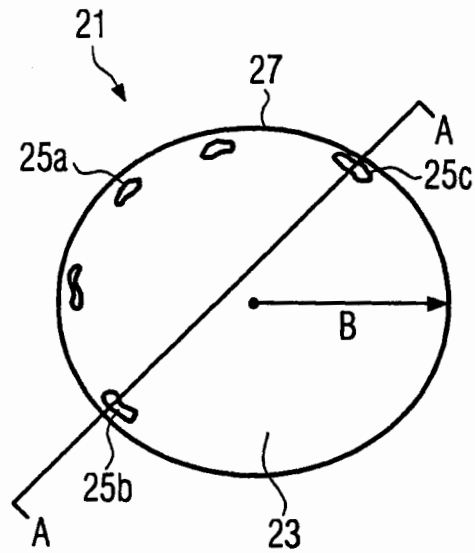



FIG. 2a

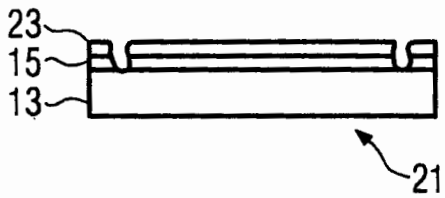



FIG. 2b

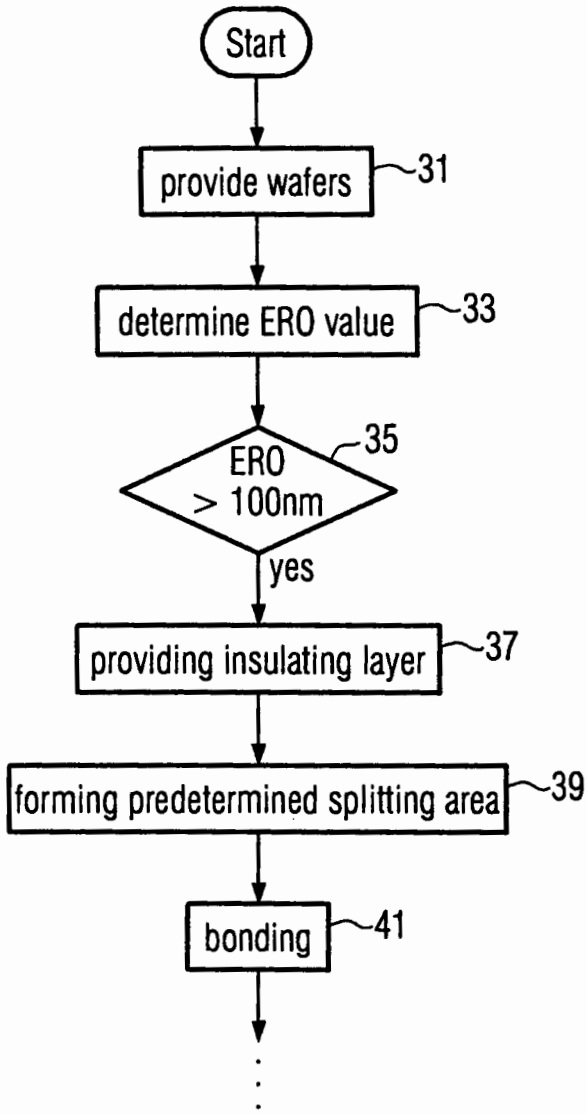

Start
provide wafers
31
determine ERO value
33
ERO
> 100nm
35
yes
providing insulating layer
37
forming predetermined splitting area
39
bonding
41

FIG. 3

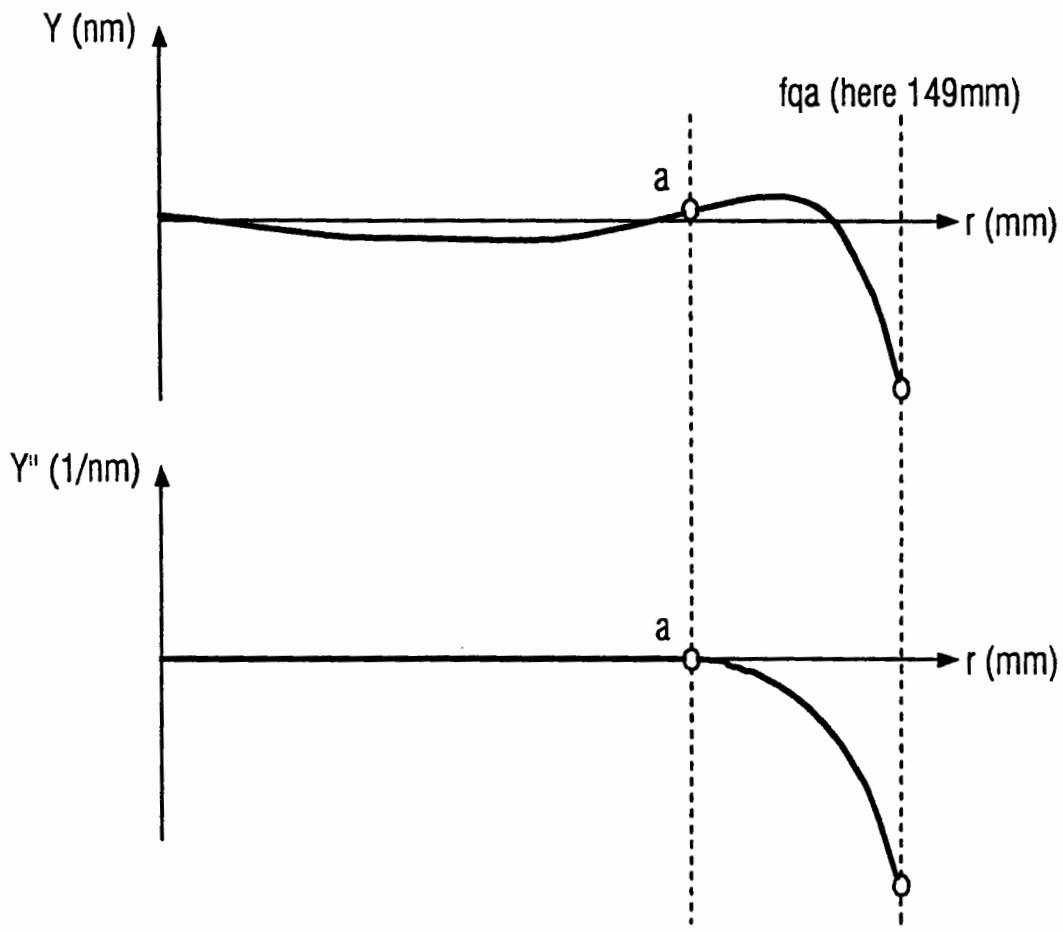



FIG. 4

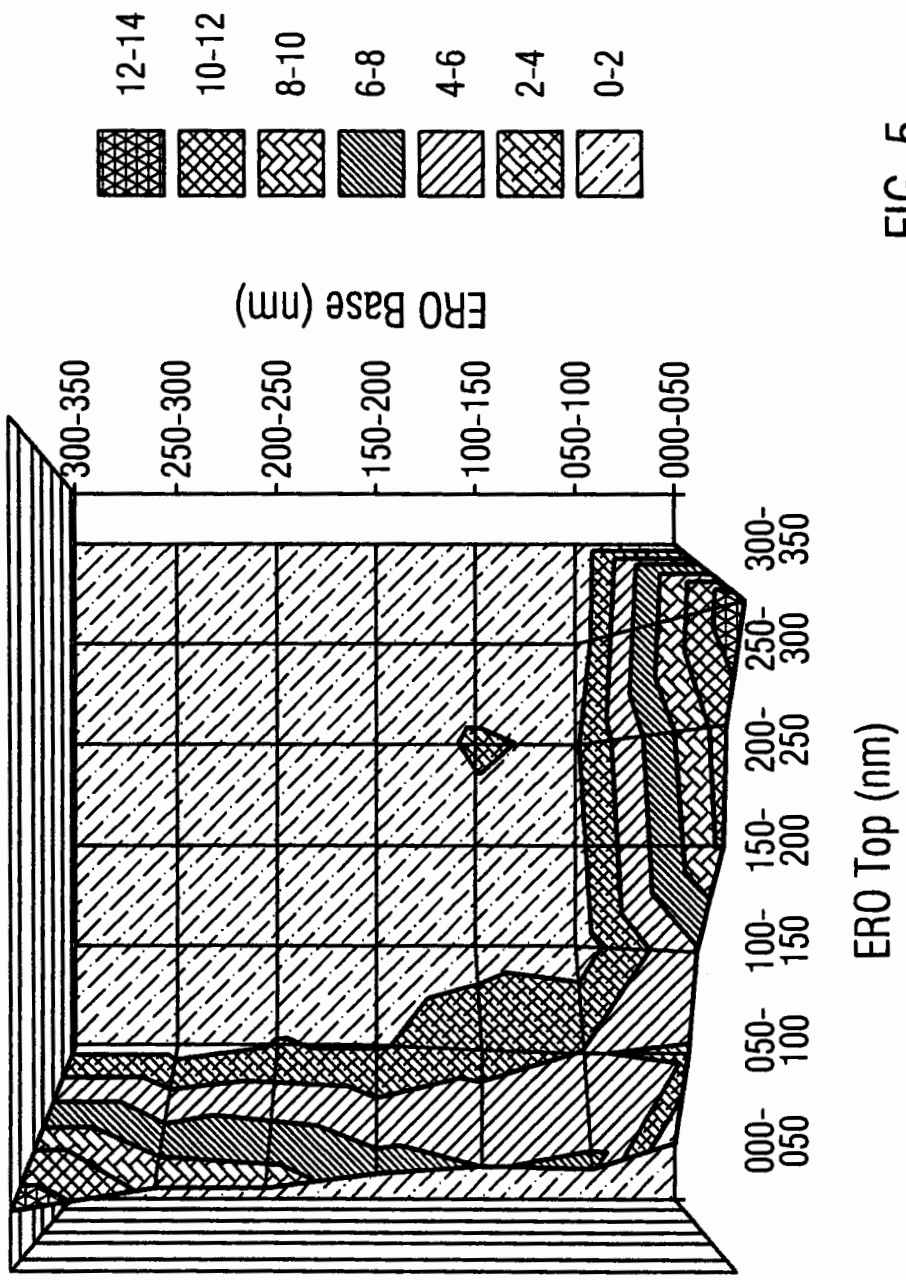

12-14
10-12
8-10
6-8
4-6
2-4
0-2
ERO Base (nm)
300-350
250-300
200-250
150-200
100-150
050-100
000-050
ERO Top (nm)
000-050
050-100
100-150
150-200
200-250
250-300
300-350

FIG. 5